In the United States Patent and Trademark Office

Filed: Sept. 16, 2003 In re Application Wenjie Li et al.

of:

For: NEGATIVE RESIST COMPOSITION WITH

FLUOROSULFONAMIDE-CONTAINING POLYMER

Serial Number: 10/663,553

Art Unit: 1713 Examiner: Roberto Rabago

DECLARATION PURSUANT TO 37 C.F.R. 1.131

Hon. Commissioner of Patents and Trademarks Alexandria, VA 22313-1450

Sir:

We. WENJIE LI and PUSHKARA RAO

- 1. We are the co-inventors of the subject matter described and claimed in the above-identified patent application.
- 2. Prior to October 21, 2002, we conceived and reduced to practice a negative resist composition comprising a polymer, the polymer comprising at least one fluorosulfonamide monomer unit having one of the following two formulae:

wherein M is a polymerizable backbone moiety; Z is a linking moiety selected from the group consisting of -C(O)O-, -C(O)-, -OC(O)-, -O-C(O)-C(O)-O-, and alkyl; P is 0 or 1; R_1 is a linear or branched alkyl group of 1 to 20 carbons; R_2 is hydrogen, fluorine, a linear or branched alkyl group of 1 to 6 carbons, or a semi- or perfluorinated linear or branched alkyl group of 1 to 6 carbons; and n is an integer from 1 to 6.

- 3. As evidence of the conception and reduction to practice of the composition of matter referred to in paragraph 2 prior to October 21, 2002, attached hereto is a true photocopy of IBM Invention Disclosure No. FIS8-2002-0362. Dates have been redacted in the preparation of the photocopies contained in the attachment.
- 4. We do hereby declare that all statements made herein of our own knowledge are true, and that all statements made on information and belief are believed to the true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under 18 U.S.C. § 1001, and that such willful false statements may jeopardize the validity or enforceability of the patent.

Respectfully Submitted,